

Errata: Fabrication of through-silicon via arrays by photo-assisted electrochemical etching and supercritical electroplating

Ho-Chiao Chuang
Hsi-Min Yang
Cheng-Xiang Wu
Jorge Sanchez
Jenq-Huey Shyu

Errata: Fabrication of through-silicon via arrays by photo-assisted electrochemical etching and supercritical electroplating

Ho-Chiao Chuang, Hsi-Min Yang, Cheng-Xiang Wu, Jorge Sanchez, and Jenq-Huey Shyu
National Taipei University of Technology, Department of Mechanical Engineering, Taipei, Taiwan

[DOI: [10.1117/1.JMM.16.1.019801](https://doi.org/10.1117/1.JMM.16.1.019801)]

This article [*J. Micro/Nanolith. MEMS MOEMS* **16**, 014501 (2017)] was originally published with an error in the title.

The term “through-silicon” appeared as “though-silicon.” All online versions of the article were corrected on 06 February 2017. The article appears correctly in print.